

AMENDMENTS TO THE CLAIMS:

13. (Currently amended) A method for producing a transparent laminate comprising:
preparing a transparent substrate;
depositing a high-refractive-index transparent thin film by a vacuum dry process;
depositing a silver transparent conductive thin film by a vacuum dry process;
repeating the depositing of the high-refractive-index transparent thin film and the
silver transparent conductive thin film at least three times to thereby form at least three
combination thin-film layers of the high-refractive-index transparent thin film and the silver
transparent conductive thin film successively laminated on a surface of said transparent
substrate; and
depositing another high-refractive-index transparent thin film on a surface of said
combination thin-film layer by the vacuum dry process,
wherein, when said silver transparent conductive thin films are deposited by the
vacuum dry process, a temperature T (K) of said transparent substrate at the time of the
deposition of said films is set to be in a range $340 \leq T \leq 410$ 390.

14. (Currently amended) A method for producing a transparent laminate comprising:
preparing a transparent substrate;
depositing a high-refractive-index transparent thin film by a vacuum dry process;
depositing a silver transparent conductive thin film by a vacuum dry process;
repeating forming of the high-refractive-index transparent thin film and the silver
transparent conductive thin film at least three times to thereby form at least three combination

thin-film layers of the high-refractive-index transparent thin film and the silver transparent conductive thin film successively laminated on a surface of said transparent substrate; and depositing another high-refractive-index transparent thin film on a surface of said combination thin-film layer by the vacuum dry process,

wherein, when said silver transparent conductive thin films are deposited by the vacuum dry process, a temperature T (K) of said transparent substrate at the time of the deposition of said films is set to be in a range $340 \leq T \leq 390$, and a deposition rate R (nm/sec) of said silver transparent conductive thin films is set to be $R = (1/40)x(T-300)\pm 0.5$.

15. (Previously added) The method of claim 13, further comprising depositing a low-refractive-index transparent thin film.

16. (Previously amended) The method of claim 15, wherein the low-refractive-index transparent thin film is deposited before any high-refractive-index thin film is deposited.

17. (Currently amended) The method of claim 15, wherein the low-refractive-index transparent thin film is deposited after all of the high-refractive-index thin films are film is deposited.

18. (Currently amended) A method of producing a plasma display filter, with the The method of claim 13, further comprising disposing said transparent laminate in front of a display portion of forming a plasma display panel filter with the transparent laminate.

19. (Previously added) The method of claim 14, further comprising depositing a low-refractive-index transparent thin film.

20. (Previously amended) The method of claim 19, wherein the low-refractive-index transparent thin film is deposited before any high-refractive-index thin film is deposited.

21. (Currently amended) The method of claim 19, wherein the low-refractive-index transparent thin film is deposited after all of the high-refractive-index thin films are film is deposited.

22. (Currently amended) The method of claim 14, further comprising disposing said transparent laminate in front of a display portion of forming a plasma display panel filter with the transparent laminate.

23. (New) The method of claim 13, wherein said vacuum dry process comprises a sputtering process.

24. (New) The method of claim 13, wherein said silver transparent conductive thin film comprises silver and 5 % by weight of gold.

25. (New) The method of claim 13, wherein said repeated depositing is repeated only three times to form three combination thin-film layers.

26. (New) The method of claim 14, wherein said vacuum dry process comprises a sputtering process.

27. (New) The method of claim 14, wherein said silver transparent conductive thin film comprises silver and 5 % by weight of gold.

28. (New) The method of claim 14, wherein said repeated depositing is repeated only three times to form three combination thin-film layers.

